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2811

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Applicant:

Justin K. Brask et al.

§ Art Unit: 2811

Serial No.: 10/626,336

§ Examiner: Ori Nadav

Filed: July 24, 2003

§ Atty Docket: ITL.1022US
P16709

For: Forming a High Dielectric Constant
Film Using Metallic Precursor

§ Assignee: Intel Corporation

§

Mail Stop AF
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

REPLY TO FINAL REJECTION

Sir:

In response to the final rejection mailed February 23, 2005, reconsideration is requested in view of the following remarks.

Date of Deposit: March 15, 2005
I hereby certify under 37 CFR 1.8(a) that this correspondence is being deposited with the United States Postal Service as **first class mail** with sufficient postage on the date indicated above and is addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

Cynthia L. Hayden
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